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(54) Title: AN ELECTRON BEAM DEVICE HAVING A RESISTIVE FOCUSING LENS STRUCTURE AND METHOD FOR MAKING SUCH A DEVICE

(57) Abstract

A resistive focusing lens structure for an electron beam device wherein the total resistance of the focusing lens structure is larger than 2.5 GΩ and the absolute value of the temperature coefficient of resistance is smaller than $250 \cdot 10^{-6} \text{K}^{-1}$. Preferably, said resistive focusing lens structure comprises a resistance layer of a fired suspension of a conductive material of a mixture of a lead ruthenate, a lead titanate and a ruthenium oxide in a glass formed of silicon dioxide, aluminum oxide and lead oxide.

